Status of µ-RWELL for FCC_ee: Pre-shower & Muon system



Marco Poli Lener on behalf of Bo, Fe, LNF, To

IDEA— $\mu\text{-}RWELL$ for pre-shower and muon apparatus

The **IDEA detector** is a general purpose detector designed for experiments at future e^+e^- colliders. **Pre-shower detector** and the Muon system are designed to be instrumented with μ -RWELL technology.

Pre-shower & Muon requirements:

Tiles: 50x50 cm² with X-Y readout

Efficiency ≥ 98%

Space resolution ≤ 100 µm (Pre-shower)

≤ 400 μm (Muon)

Particle Flux < Hz/cm² (Pre-shower)

< 1kHZ/cm² (Muon)

Instrumented Surface/FEE:

130 m², 520 det., 3×10⁵ ch. (0.4 mm strip pitch)

1500 m², 6000 det., 5×10⁶ ch. (1.2 mm strip pitch)

Mass production \rightarrow Technology Transfer to Industry

FEE Cost reduction → custom made ASIC (TIGER,)

Italian Institute involved: Laboratori Nazionali di Frascati, Bologna, Ferrara, Torino





G. Bencivenni et al., The micro-Resistive WELL detector: a compact sparkprotected single amplification-stage MPGD, 2015 JINST 10 P02008



The μ -RWELL is a resistive MPGD composed of two elements:

- Cathode
- μ-RWELL_PCB:

The µ-RWELL

- a WELL patterned kapton foil (w/Cu-layer on top) acting as amplification stage
- − a resisitive DLC layer^(*) w/ ρ ~10÷100 MΩ/ \Box
- a standard readout PCB with pad/strip segmentation

(*) DLC foils are currently provided by the Japan Company – BeSputter



The **"WELL"** acts as a **multiplication channel** for the ionization produced in the drift gas gap.

The **resistive stage** ensures the **spark amplitude quenching**. **Drawback:** capability to stand high particle fluxes reduced, but **largely recovered** with appropriate **grounding schemes** of the **resistive layer**



u-RWELL R&D History





Layout 1D optimization

R&D for FCC: 1D R/out



Resistivity Scan @ fixed pitch



Pre-preg thickness= 50 um Resistivity= 10 ÷80 MΩ/□ Strip pitch= 0.4 mm Strip width = 0.150 mm Ratio p/w= 2.66

15/10/2024

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R&D for FCC: 1D R/out

R/O pitch scan @ fixed resistivity



Active area= 400x50 mm2 Pre-preg thickness= 50 um Resistivity= 30 M Ω / Strip pitch= 0.4-1.6 mm Strip width = 0.15 mm p/w ratio= 2.66 - 10.66

15/10/2024



Layout 2D optimization

TB Analysis finalization -2D layouts – 10x10 cm²





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TB Analysis finalization -2D layouts





The results of TB-22-23, where the 2D layouts have been compared, gaving the following results: **2x1D layout**: spatial resolution < 200um (pitch 0.8 mm), low voltage operating point ~520V, efficiency ≥98% (large eff. plateau) **CS layout**: spatial resolution <200um (with pitch 1.2 mm), very high voltage operating point, ≥ 600V, efficiency ≥98% **Top layout**: spatial resolution < 200um (pitch 0.8 mm), low voltage operating point ~520V, efficiency ~ 70% (dead-zone)

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R&D program 2024

The production of the 2023 & 2024 layouts has been delayed due to the increased workload at the Rui's workshop

Solutions under study:

- **1.** μ -RWELL pitch optimization \rightarrow This study was done with GEM detectors but never with uRWELL \rightarrow well pitch from 140 μ m to 90 μ m with an increase in gain of about a factor of 2. Designed at the beginning of 2024 & detector delivery in Sept. 2024.
- 2. Micro-RGroove layout → new layout, where the amplification stage is not based on the «wells» but on the «grooves». This facilitates the realization of the strip readout on the top, without introducing dead-zones (introduced by Z. Yi in RD51). Designed at the end of 2023 & detector delivery in Sept. 2024.
- 3. CS layout with pad → new layout, where the readout PCB is not segmented in strips but with pad. This choice allows to collect all the charge on a single readout electrode with a small increase of FFE channels (30%). With pad of few cm2 a spatial resolution of ~300 um has been achieved (introduced by M. lodice in RD51). Designed in Sept. 2024.
- 4. Hybrid CS → CS + GEM pre-amplification stage, to lower the operating point, greatly improving the RWELL stability and maintaining high spatial performance with millimetric pitches.





Z. Yi

<u>M. Iodice</u>



Call for interest



μ-RWELL

- R&D is on going to optmize the detector layout for FCC_ee. LNF responsible for R&D.
- Considering the huge costruction effort, the detector production will be shared among several institute. Collabation is welcome.

Front-end Electronics & Off-detector

- New chip is needed for this technology. Bo/To responsible for the R&D. Collaboration is welcome.

Software

- Simulation, recostruction and software is needed. Bo/Fe responsible for the simulation. Collaboration is welcome.

There are multiple options to contribute, with the possibility of leading contributions in many areas.

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Thanks for your attention